10/743,809, 9-5-05, RFA.

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	"4374066".pn.	US-PGPUB; USPAT	OR	ON	2005/09/05 18:44
L2	439	568/28.ccls.	US-PGPUB; USPAT	OR	ON	2005/09/05 18:44
L3	34	568/28.ccls. and sulfonium	US-PGPUB; USPAT	OR	ON	2005/09/05 18:56
L4	14	568/28.ccls. and sulfonium and sulfonyl	US-PGPUB; USPAT	OR	ON	2005/09/05 19:03
L5	5	430/921.ccls. and (sulfonium with sulfonyl)	US-PGPUB; USPAT	OR	ON	2005/09/05 19:06
L6	87	430/270.1.ccls. and (sulfonium with sulfonyl)	US-PGPUB; USPAT	OR	ON	2005/09/05 19:07
L7	436	sulfonium with sulfonyl	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/05 19:08
L8	113	sulfonium with sulfonyl and (photoacid or acid adj generator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/05 19:08

10/743,809, 9-5-05, L9A } SO_2-CF_2 — open cl 3
CA Rpg. file strucsearch FG } $-SO_2-$⬡ cl 7
$-SO_2-Nb$ cl 8
$-SO_2-$⬠ cl 7.
cls 3, 7, 8
only Hits for my Application.

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     (FILE 'HOME' ENTERED AT 20:30:06 ON 05 SEP 2005)

     FILE 'REGISTRY' ENTERED AT 20:30:11 ON 05 SEP 2005
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L2              STRUCTURE UPLOADED
L3              STRUCTURE UPLOADED
L4              STRUCTURE UPLOADED
L5            4 S L1 FULL
L6            6 S L2 FULL
L7            2 S L3 FULL
L8            0 S L4 FULL

     FILE 'CAPLUS' ENTERED AT 20:31:55 ON 05 SEP 2005
               S L4

     FILE 'REGISTRY' ENTERED AT 20:32:02 ON 05 SEP 2005
L9            0 S L4

     FILE 'CAPLUS' ENTERED AT 20:32:03 ON 05 SEP 2005
L10           0 S L9
L11           1 S L5

=> s l6
L12           1 L6

=> d bib

L12  ANSWER 1 OF 1  CAPLUS  COPYRIGHT 2005 ACS on STN
AN   2005:219970  CAPLUS
DN   142:306448
TI   Onium salt compound and radiation-sensitive resin composition
IN   Yoneda, Eiji; Wang, Yong; Nishimura, Yukio
PA   Japan
SO   U.S. Pat. Appl. Publ., 85 pp.
     CODEN: USXXCO
DT   Patent
LA   English
FAN.CNT 2
     PATENT NO.          KIND   DATE        APPLICATION NO.         DATE
     ---------------     ----   --------    --------------------    --------
PI   US 2005053861        A1    20050310    US 2003-743809          20031224
     JP 2004250427        A2    20040909    JP 2003-182089          20030626
     JP 2005104956        A2    20050421    JP 2003-423516          20031219
PRAI JP 2002-373531       A     20021225
     JP 2002-373625       A     20021225
     JP 2003-182089       A     20030626
     JP 2003-315010       A     20030908
OS   MARPAT 142:306448


=> s l7
L13           1 L7

=> d bib

L13  ANSWER 1 OF 1  CAPLUS  COPYRIGHT 2005 ACS on STN
AN   2005:219970  CAPLUS
DN   142:306448
TI   Onium salt compound and radiation-sensitive resin composition
IN   Yoneda, Eiji; Wang, Yong; Nishimura, Yukio
PA   Japan
SO   U.S. Pat. Appl. Publ., 85 pp.
     CODEN: USXXCO
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10/743,809, 9-5-05, CA Reg. File STNE. search. REA.

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      FILE 'REGISTRY' ENTERED AT 17:22:35 ON 05 SEP 2005
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L2                STRUCTURE UPLOADED
L3                STRUCTURE UPLOADED
L4                STRUCTURE UPLOADED
L5                STRUCTURE UPLOADED
L6              0 S L1 FULL
L7              0 S L2 FULL
L8              7 S L3 FULL
L9             17 S L4 FULL
L10             2 S L5 FULL

      FILE 'CAPLUS' ENTERED AT 17:30:44 ON 05 SEP 2005
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L12             9 S L9
L13             1 S L10

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l1 = Form 1
l2 " 2
l3 " 4
l4 " 5
l5 " 6

} From SPEC.

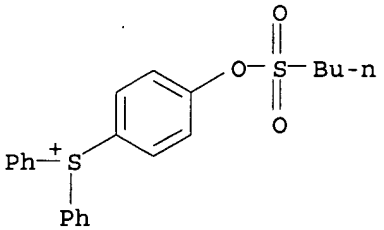
L11 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2005:219970 CAPLUS
DN 142:306448
TI Onium salt compound and radiation-sensitive resin composition
IN Yoneda, Eiji; Wang, Yong; Nishimura, Yukio
PA Japan
SO U.S. Pat. Appl. Publ., 85 pp.
CODEN: USXXCO
DT Patent
LA English
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2005053861	A1	20050310	US 2003-743809	20031224
	JP 2004250427	A2	20040909	JP 2003-182089	20030626
	JP 2005104956	A2	20050421	JP 2003-423516	20031219
PRAI	JP 2002-373531	A	20021225		
	JP 2002-373625	A	20021225		
	JP 2003-182089	A	20030626		
	JP 2003-315010	A	20030908		

OS MARPAT 142:306448
AB An onium salt compound having a cation moiety of formula I (A = I, S; m = 1 or 2; n = 0 or 1; x = 1-10; and Ar1, Ar2 = aromatic hydrocarbon group; and P = -O-SO2R, -O-S(O)R, -SO2R; R = H, (substituted) alkyl group, or a (substituted) alicyclic hydrocarbon group)is disclosed. The onium salt compound is suitable as a photoacid generator for photoresists of a pos.-tone radiation-sensitive resin composition The pos.-tone radiation-sensitive resin composition containing this compound is useful as a chemical-amplified photoresist exhibiting high resolution at high sensitivity, responsive to various radiations, and having outstanding storage stability.
IT **753454-43-2P 847799-97-7P**
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(onium salt compound as photoacid generator for radiation-sensitive resin composition)
RN 753454-43-2 CAPLUS
CN Sulfonium, [4-[(butylsulfonyl)oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 753454-42-1
CMF C22 H23 O3 S2



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S

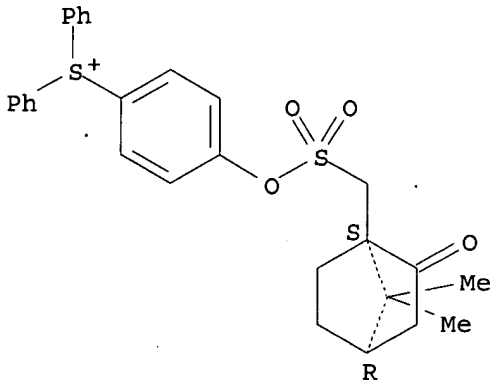
$^{-}O_3S-(CF_2)_3-CF_3$

RN 847799-97-7 CAPLUS
CN Sulfonium, [4-[[[[(1S,4R)-7,7-dimethyl-2-oxobicyclo[2.2.1]hept-1-yl]methyl]sulfonyl]oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847799-96-6
CMF C28 H29 O4 S2

Absolute stereochemistry.



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

L11 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2004:741785 CAPLUS
DN 141:268555
TI Onium salts for radiation-sensitive acid generator for positive photoresist compositions
IN Yoneda, Eiji; Nishimura, Yukio; Wang, Yong
PA JSR Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 48 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004250427	A2	20040909	JP 2003-182089	20030626
	US 2005053861	A1	20050310	US 2003-743809	20031224
PRAI	JP 2002-373625	A	20021225		
	JP 2002-373531	A	20021225		
	JP 2003-182089	A	20030626		
	JP 2003-315010	A	20030908		

OS MARPAT 141:268555

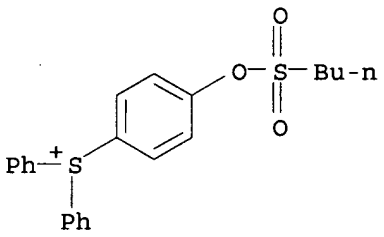
AB The onium salt has cationic portion represented with (Ar2)n-A+-(Ar1)m-(OZ)x (A = I, S; m = 1,2 ; n = 0, 1; (m+n) = 2; x = integer 1-10; Ar1-2 = mono-valent C6-20 aromatic hydrocarbon, mono-valent C3-20 heterocyclic ring, 3-8 membered ring residue with Ar1, Ar2, and A; Z = -SO2R1, -S(O)R2; R1-2 = H, C1-20 alkyl, mono-valent C3-20 alicyclic, etc.). The onium salt provides photoresist composition of high sensitivity and good storageability.

IT **753454-43-2P 753454-47-6P 753454-49-8P**
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(onium salts for radiation-sensitive acid generator for pos. photoresist compns.)

RN 753454-43-2 CAPLUS
CN Sulfonium, [4-[(butylsulfonyl)oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 753454-42-1
CMF C22 H23 O3 S2



CM 2

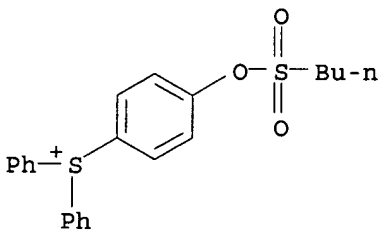
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 753454-47-6 CAPLUS
CN Sulfonium, [4-[(butylsulfonyl)oxy]phenyl]diphenyl-, salt with α,α,β,β-tetrafluorobicyclo[2.2.1]heptane-2-ethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

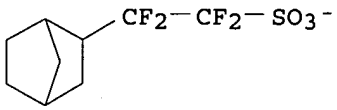
CM 1

CRN 753454-42-1
CMF C22 H23 O3 S2



CM 2

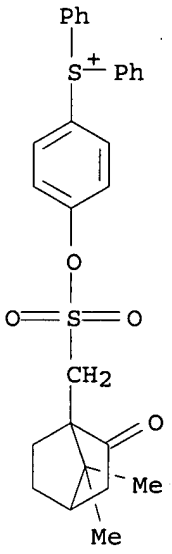
CRN 474516-37-5
CMF C9 H11 F4 O3 S



RN 753454-49-8 CAPLUS
CN Sulfonium, [4-[[[(7,7-dimethyl-2-oxobicyclo[2.2.1]hept-1-yl)methyl]sulfonyl]oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

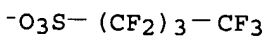
CM 1

CRN 753454-48-7
CMF C28 H29 O4 S2



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S



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L12 ANSWER 1 OF 9 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2005:219970 CAPLUS
DN 142:306448
TI Onium salt compound and radiation-sensitive resin composition
IN Yoneda, Eiji; Wang, Yong; Nishimura, Yukio
PA Japan
SO U.S. Pat. Appl. Publ., 85 pp.
CODEN: USXXCO
DT Patent
LA English
FAN.CNT 2

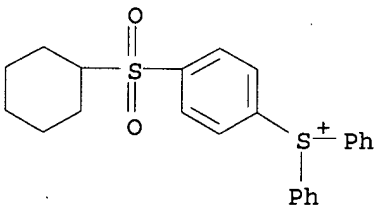
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2005053861	A1	20050310	US 2003-743809	20031224
	JP 2004250427	A2	20040909	JP 2003-182089	20030626
	JP 2005104956	A2	20050421	JP 2003-423516	20031219
PRAI	JP 2002-373531	A	20021225		
	JP 2002-373625	A	20021225		
	JP 2003-182089	A	20030626		
	JP 2003-315010	A	20030908		

myappl

OS MARPAT 142:306448
AB An onium salt compound having a cation moiety of formula I (A = I, S; m = 1 or 2; n = 0 or 1; x = 1-10; and Ar1, Ar2 = aromatic hydrocarbon group; and P = -O-SO2R, -O-S(O)R, -SO2R; R = H, (substituted) alkyl group, or a (substituted) alicyclic hydrocarbon group)is disclosed. The onium salt compound is suitable as a photoacid generator for photoresists of a pos.-tone radiation-sensitive resin composition The pos.-tone radiation-sensitive resin composition containing this compound is useful as a chemical-amplified photoresist exhibiting high resolution at high sensitivity, responsive to various radiations, and having outstanding storage stability.
IT **847800-01-5P 847800-05-9P**
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(onium salt compound as photoacid generator for radiation-sensitive resin composition)
RN 847800-01-5 CAPLUS
CN Sulfonium, [4-(cyclohexylsulfonyl)phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847800-00-4
CMF C24 H25 O2 S2



CM 2

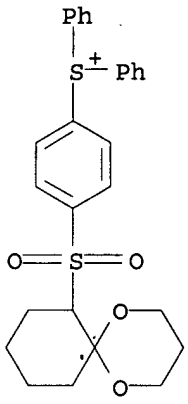
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847800-05-9 CAPLUS
CN Sulfonium, [4-(1,5-dioxaspiro[5.5]undec-7-ylsulfonyl)phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847800-04-8
CMF C27 H29 O4 S2



CM 2

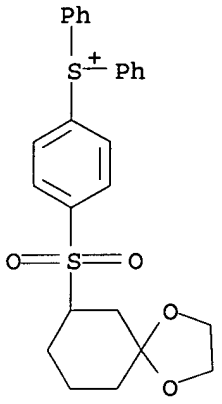
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

IT **847799-76-2P**
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(preparation of onium salt compound as photoacid generator for radiation-sensitive resin composition)
RN 847799-76-2 CAPLUS
CN Sulfonium, [4-(1,4-dioxaspiro[4.5]dec-7-ylsulfonyl)phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847799-75-1
CMF C26 H27 O4 S2



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

L12 ANSWER 2 OF 9 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1997:599494 CAPLUS
DN 127:191198
TI Photoinitiators and photoinitiator compositions and photocurable hybrid resin compositions
IN Toba, Yasumasa; Tanaka, Yasuhiro; Yasuike, Madoka
PA Toyo Ink Mfg. Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 31 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

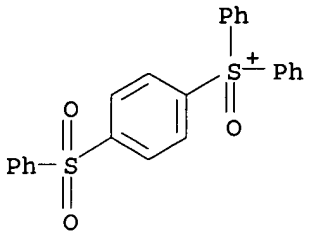
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 09183961	A2	19970715	JP 1995-342494	19951228
PRAI JP 1995-342494		19951228		

OS MARPAT 127:191198
AB The photoinitiator compns., having a high curing rate, contain sulfoxonium borates R1R2R3S+(O)·(BXmZn)- (R1-R3 = C6-20 aryl which may be substituted by halo, OH, NO2, CN, NH2, alkyl, alkoxy, aralkyloxy, aryl, aryloxy, aralkyl group; X = F, Cl; Z = Ph group substituted by ≥2 F, CN, NO2, CF3; m = 0-3; n = 1-4; m + n = 4). Thus, a composition containing 100 parts an epoxy resin (ERL 4221) and 3 parts triphenylsulfoxonium tetrakis(pentafluorophenyl)borate was irradiated by UV to give a cured film.
IT **194293-67-9 194293-75-9**
RL: CAT (Catalyst use); USES (Uses)
(sulfoxonium borate photoinitiators and photocurable hybrid resin compns.)
RN 194293-67-9 CAPLUS
CN Sulfoxonium, diphenyl[4-(phenylsulfonyl)phenyl]-, tetrakis(pentafluorophenyl)borate(1-) (9CI) (CA INDEX NAME)

CM 1

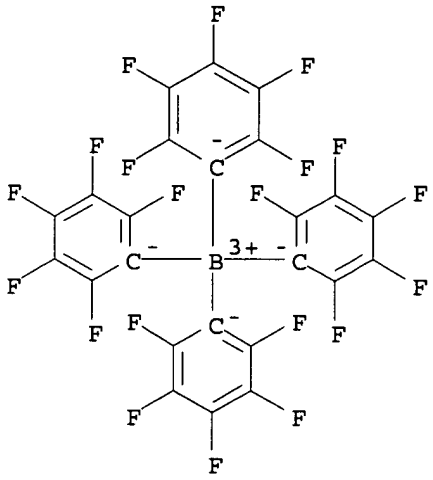
CRN 139572-76-2

CMF C24 H19 O3 S2



CM 2

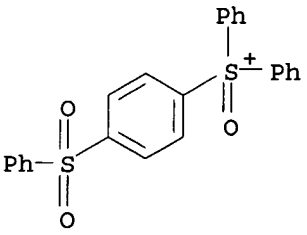
CRN 47855-94-7
CMF C24 B F20
CCI CCS



RN 194293-75-9 CAPLUS
CN Sulfoxonium, diphenyl[4-(phenylsulfonyl)phenyl]-, tetrakis[4-(trifluoromethyl)phenyl]borate(1-) (9CI) (CA INDEX NAME)

CM 1

CRN 139572-76-2
CMF C24 H19 O3 S2



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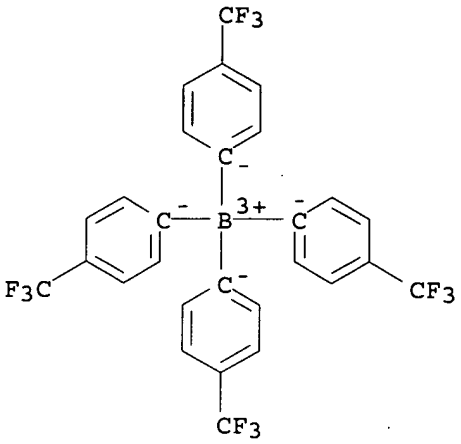
CRN 47823-82-5

CMF C28 H16 B F12
CCI CCS



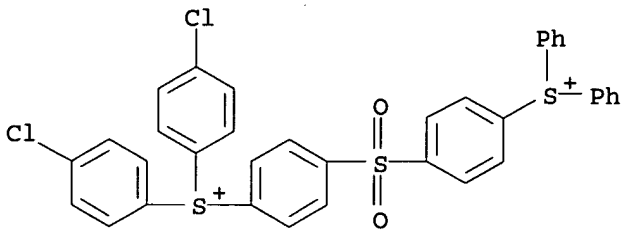
L12 ANSWER 3 OF 9 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1996:256323 CAPLUS
DN 124:318806
TI Photopolymerization initiators, radiation-curable compositions, and their cured products
IN Abe, Tetsuya; Yokoshima, Minoru
PA Nippon Kayaku Kk, Japan
SO Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08041116	A2	19960213	JP 1994-193778	19940727
	JP 3424772	B2	20030707		
PRAI	JP 1994-193778		19940727		

OS MARPAT 124:318806
AB Sulfonium- and sulfoxonium-type photopolymn. initiators are synthesized and are used in radiation curable epoxy resins. Thus, compound I was oxidized with hydrogen peroxide to give compound II; II 1.5, Celloxide 2021 80, and EHPE 3150 20 parts were mixed and cured by UV to show transparency, storage stability, gloss, no odor, and tack free 23 mJ/cm2.
IT **176310-56-8P 176310-62-6P**
RL: CAT (Catalyst use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(preparation of photopolymn. initiators and radiation-curable compns.)
RN 176310-56-8 CAPLUS
CN Sulfonium, bis(4-chlorophenyl)[4-[[4-(diphenylsulfonio)phenyl]sulfonyl]phenyl]-, bis[hexafluorophosphate(1-)] (9CI) (CA INDEX NAME)

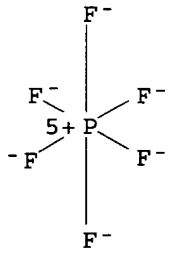
CM 1

CRN 176310-55-7
CMF C36 H26 Cl2 O2 S3



CM 2

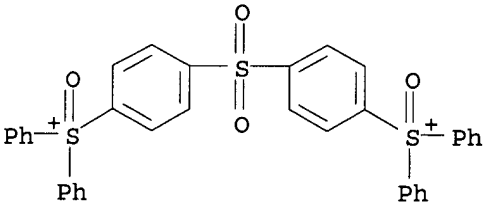
CRN 16919-18-9
CMF F6 P
CCI CCS



RN 176310-62-6 CAPLUS
CN Sulfoxonium, (sulfonyldi-4,1-phenylene)bis[diphenyl-, bis[hexafluorophosphate(1-)] (9CI) (CA INDEX NAME)

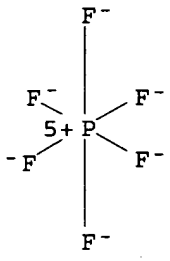
CM 1

CRN 176310-61-5
CMF C36 H28 O4 S3



CM 2

CRN 16919-18-9
CMF F6 P
CCI CCS



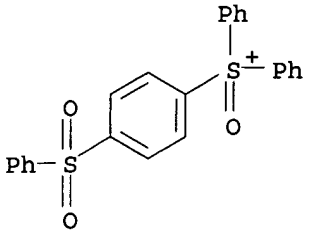
L12 ANSWER 4 OF 9 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1992:131247 CAPLUS
DN 116:131247
TI Preparation of triarylsulfoxonium salts and their use as initators for cationic photopolymerization
IN Irving, Edward; Taylor, David Alan; Lunn, Robert James; Innocenzi, John Paul; Haines, Alan Hugh
PA CIBA Ltd., Switz.
SO Brit. UK Pat. Appl., 24 pp.
CODEN: BAXXDU
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	GB 2238787	A1	19910612	GB 1989-27530	19891206
	GB 2238787	B2	19930303		
	JP 03271270	A2	19911203	JP 1990-333442	19901129
	DE 4038536	A1	19910613	DE 1990-4038536	19901203
	CA 2031428	AA	19910607	CA 1990-2031428	19901204
	FR 2655338	A1	19910607	FR 1990-15147	19901204
	FR 2655338	B1	19921002		
	US 5576461	A	19961119	US 1990-622905	19901206
PRAI	GB 1989-27530	A	19891206		

OS MARPAT 116:131247
AB R1R2R3S+O X- [I; R1, R2, R3 = (substituted) C6-10 aryl, X = anion], useful as initiators for cationic polymerization of compds. such as diepoxides in the manufacture of coatings, are prepared by oxidation of the corresponding sulfonium salts using a peracid under basic conditions in a nonketone solvent. Use of the basic conditions and nonketone solvent improves the yield and eliminates contamination of the product with the starting material. Thus, a solution of 5.1 g NaOH and 6.7 g 30% aqueous H2O2 solution in 50 mL water was added dropwise to 300 mL MeOH containing 5.6 g (4-MeOC6H4)Ph2SPF6 and 6.1 g p-toluenesulfonyl chloride at 15° with stirring, and the mixture was allowed to warm to room temperature overnight to give 84% yield I (R1 = 4-MeOC6H4, R2 = R3 = Ph, X = PF6) (II). Irradiation of a mixture containing 100 parts bisphenol A diglycidyl ether and 3 parts II on tin plate with a 5000-W metal halide lamp 75 cm from the plate provided a tack-free coating in 2 mins.
IT **139572-77-3P**
RL: PREP (Preparation)
(manufacture of, for cationic photopolymn. catalysts)
RN 139572-77-3 CAPLUS
CN Sulfoxonium, diphenyl[4-(phenylsulfonyl)phenyl]-, hexafluorophosphate(1-) (9CI) (CA INDEX NAME)

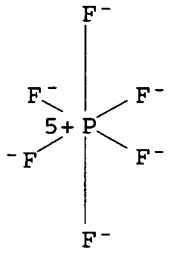
CM 1

CRN 139572-76-2
CMF C24 H19 O3 S2



CM 2

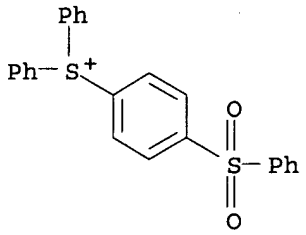
CRN 16919-18-9
CMF F6 P
CCI CCS



L12 ANSWER 5 OF 9 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1985:167245 CAPLUS
DN 102:167245
TI Recent advances in thermally and photochemically initiated cationic polymerization
AU Crivello, James V.; Lee, J. L.
CS Gen. Electr. Corp. Res. and Dev., Schenectady, NY, 12301, USA
SO Polymer Journal (Tokyo, Japan) (1985), 17(1), 73-83
CODEN: POLJB8; ISSN: 0032-3896
DT Journal
LA English
AB Classes of arylsulfonium salts are discussed which have enhanced efficiency as photoinitiators or thermal initiators of cationic polymerization One of these compds., p-PhSC6H4SPh2+AsF6- [75482-17-6], was identified as a component of the Friedel-Crafts reaction of C6H6 with S2Cl2. Similar compds., of formula ArSPh2+AsF6- (e.g., Ar = p-PhOC6H4, m-PhSC6H4, and p-PhSO2C6H4) and cyclic analogs (e.g., S-phenyldibenzothiophenium hexafluoroarsenate [82617-08-1]), were also prepared and characterized. Other classes (e.g., dialkylphenacylsulfonium salts, ArCOCH2SR2+X-) are also described; one class, characterized by 4-hydroxy-3,5-dimethoxyphenyldimethylsulfonium hexafluorophosphate [95896-72-3], is especially suited as thermal initiators. The activities of the initiators were tested in the cationic polymns. of limonene dioxide, cyclohexene oxide, and styrene oxide.
IT **75482-29-0**
RL: USES (Uses)
(photoinitiators, for cationic polymerization of epoxides)
RN 75482-29-0 CAPLUS
CN Sulfonium, diphenyl[4-(phenylsulfonyl)phenyl]-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

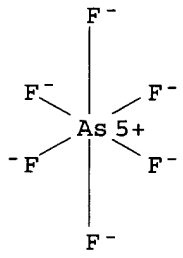
CM 1

CRN 47572-95-2
CMF C24 H19 O2 S2



CM 2

CRN 16973-45-8
CMF As F6
CCI CCS



L12 ANSWER 6 OF 9 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1983:180499 CAPLUS
DN 98:180499
TI Triarylsulfonium salts
IN Crivello, James V.; Lee, Julia L.
PA General Electric Co., USA
SO U.S., 8 pp. Cont.-in-part of U.S. Ser. No. 79,692, abandoned.
CODEN: USXXAM
DT Patent
LA English
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 4374066	A	19830215	US 1980-200769	19801027
	ZA 8005273	A	19811125	ZA 1980-5273	19800826
	GB 2061280	A	19810513	GB 1980-29024	19800909
	GB 2061280	B2	19840516		
	CA 1120181	A1	19820316	CA 1980-361443	19800925
	FR 2466457	A1	19810410	FR 1980-20689	19800926
	FR 2466457	B1	19850308		
	JP 56055420	A2	19810516	JP 1980-133103	19800926
	JP 63036332	B4	19880720		
	ES 495420	A1	19811016	ES 1980-495420	19800926
	AU 8062780	A1	19810409	AU 1980-62780	19800929
	AU 539699	B2	19841011		
	BR 8006335	A	19810414	BR 1980-6335	19800929
PRAI	US 1979-79692	A2	19790928		

AB Triarylsulfonium salts such as I [75482-17-6] are prepared by a method based on the reaction of an aromatic hydrocarbon S2Cl2, and Cl in the

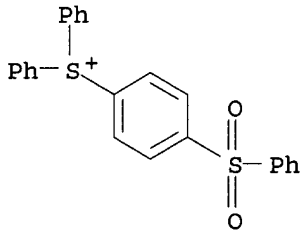
presence of a Friedel-Crafts catalyst. The triarylsulfonium salts are used as cationic photoinitiaters to effect the deep-section cure of organic resin compns. Thus, a mixture of Ph2S [139-66-2] 37.2, AlCl3 13.34, and Cl 9.5 parts was stirred and poured onto 500 parts ice. The semisolid was washed with H2O. Then 27.8 parts AsF6- K+ and 500 parts H2O were added to the residue and the mixture stirred at 30° for 1 h. The product was washed with H2O then with anhydrous Et2O and dried at 60° for 16 h. The product was then recrystd. from 95% EtOH to give 31% yield of I having m.p. 77-87°. Films from a 3% solution of I in 3,4-epoxycyclohexylmethyl 3',4'-epoxycyclohexane carboxylate [2386-87-0] were radiation-cured in 1 min to a maximum thickness of 50 mils, compared with 15 mils for a similar film containing Ph3S+ AsF6-.

IT **75482-29-0P**
RL: PREP (Preparation)
(preparation of, as photoinitiators for deep cure of polymers)

RN 75482-29-0 CAPLUS
CN Sulfonium, diphenyl[4-(phenylsulfonyl)phenyl]-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

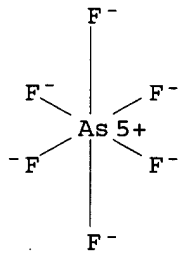
CM 1

CRN 47572-95-2
CMF C24 H19 O2 S2



CM 2

CRN 16973-45-8
CMF As F6
CCI CCS



L12 ANSWER 7 OF 9 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1981:516453 CAPLUS
DN 95:116453
TI Deep-setting photohardenable compositions
IN Crivello, James Vincent; Lam, Julia Hingwai
PA General Electric Co., USA
SO Ger. Offen., 23 pp.
CODEN: GWXXBX
DT Patent

LA German
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3035807	A1	19810409	DE 1980-3035807	19800923
	DE 3035807	C2	19930401		
	ZA 8005273	A	19811125	ZA 1980-5273	19800826
	GB 2061280	A	19810513	GB 1980-29024	19800909
	GB 2061280	B2	19840516		
	CA 1120181	A1	19820316	CA 1980-361443	19800925
	FR 2466457	A1	19810410	FR 1980-20689	19800926
	FR 2466457	B1	19850308		
	JP 56055420	A2	19810516	JP 1980-133103	19800926
	JP 63036332	B4	19880720		
	ES 495420	A1	19811016	ES 1980-495420	19800926
	AU 8062780	A1	19810409	AU 1980-62780	19800929
	AU 539699	B2	19841011		
	BR 8006335	A	19810414	BR 1980-6335	19800929
PRAI	US 1979-79692	A	19790928		

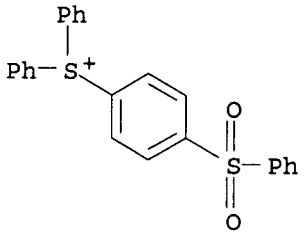
AB The sulfonium compds. 4-RC6H4S+Ph2 AsF6- (R = PhS, PhSO, or PhSO2) and 4-(PhS)C6H4S+Ph2 PF6- [75482-18-7] are useful as initiators for the polymerization of photohardenable epoxy, phenolic, vinyl, and other compds. Thus, Ph2S [139-66-2] was treated with Cl in the presence of AlCl3, and the reaction product was treated with KAsF6 [17029-22-0] to prepare 4-(PhS)C6H4S+Ph2 AsF6- (I) [75482-17-6]. A 3% solution containing 3,4-epoxycyclohexylmethyl 3,4-epoxycyclohexanecarboxylate (II) and I was hardened by UV light as a 1270-μ layer. With Ph3S+ AsF6- as the initiator instead of I, the maximum thickness of II for satisfactory hardening was 254-381 μ.

IT **75482-29-0**
RL: CAT (Catalyst use); USES (Uses)
(catalysts, for photopolymn. and photocrosslinking)

RN 75482-29-0 CAPLUS
CN Sulfonium, diphenyl[4-(phenylsulfonyl)phenyl]-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

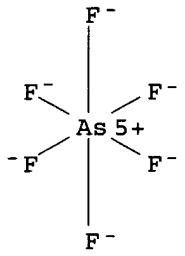
CM 1

CRN 47572-95-2
CMF C24 H19 O2 S2



CM 2

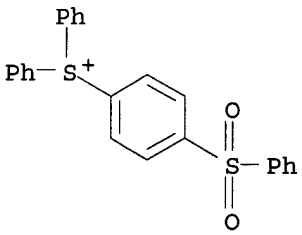
CRN 16973-45-8
CMF As F6
CCI CCS



L12 ANSWER 8 OF 9 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1980:605102 CAPLUS
DN 93:205102
TI Complex triarylsulfonium salt photoinitiators. II. The preparation of several new complex triarylsulfonium salts and the influence of their structure in photoinitiated cationic polymerization
AU Crivello, J. V.; Lam, J. H. W.
CS Gen. Electr. Corp. Res. Dev. Cent., Schenectady, NY, 12301, USA
SO Journal of Polymer Science, Polymer Chemistry Edition (1980), 18(8), 2697-714
CODEN: JPLCAT; ISSN: 0449-296X
DT Journal
LA English
AB Complex triarylsulfonium salts containing thiophenoxy chromophores were prepared
The effects of the position of the thiophenoxy group on the rate of photolysis and on the photoinitiated cationic polymerization of various monomers
were investigated. Salts in which the thiophenoxy group was oxidized to the sulfoxide and the sulfone also were prepared to examine the effects of the oxidation state of the S-bearing chromophore on the efficiencies in photoinitiated cationic polymerization All complex salts having extended conjugation not impeded by positional isomerization or blocked by oxidation of the thiophenoxy group are more reactive than the corresponding triphenylsulfonium salts in cationic polymerization
IT **75482-29-0**
RL: CAT (Catalyst use); USES (Uses)
(catalysts, for cationic photochem. polymerization)
RN 75482-29-0 CAPLUS
CN Sulfonium, diphenyl[4-(phenylsulfonyl)phenyl]-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

CM 1

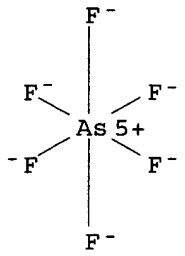
CRN 47572-95-2
CMF C24 H19 O2 S2



CM 2

CRN 16973-45-8

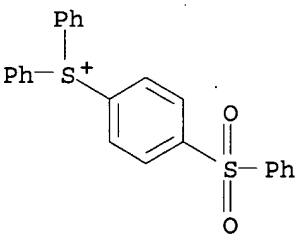
CMF As F6
CCI CCS



L12 ANSWER 9 OF 9 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1972:85504 CAPLUS
DN 76:85504
TI Electrochemistry of organic sulfur compounds. III. Novel anodic synthesis of a sulfonium salt from diphenyl sulfide
AU Uneyama, Kenji; Torii, Sigeru
CS Sch. Eng., Okayama Univ., Okayama, Japan
SO Journal of Organic Chemistry (1972), 37(3), 367-9
CODEN: JOCEAH; ISSN: 0022-3263
DT Journal
LA English
AB Ph2S, dissolved in MeCN containing LiClO4, was electrolyzed at 30° to give diphenyl [p-(phenylthio)phenyl] sulfonium (I), Ph2SO, and 1,4-bis(phenylthio)benzene. Sulfonium salt I predominated in the absence of water, while Ph2SO increased as the concentration of H2O was raised.
IT **32958-91-1P**
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation of)
RN 32958-91-1 CAPLUS
CN Sulfonium, diphenyl[4-(phenylsulfonyl)phenyl]-, perchlorate (9CI) (CA INDEX NAME)

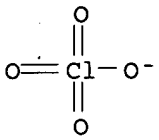
CM 1

CRN 47572-95-2
CMF C24 H19 O2 S2



CM 2

CRN 14797-73-0
CMF Cl O4



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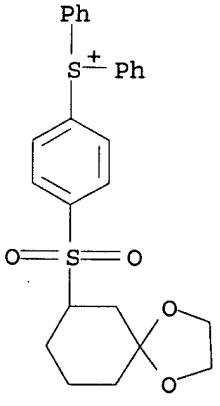
L13 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2005:219970 CAPLUS
DN 142:306448
TI Onium salt compound and radiation-sensitive resin composition
IN Yoneda, Eiji; Wang, Yong; Nishimura, Yukio
PA Japan
SO U.S. Pat. Appl. Publ., 85 pp.
CODEN: USXXCO
DT Patent
LA English
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2005053861	A1	20050310	US 2003-743809	20031224
	JP 2004250427	A2	20040909	JP 2003-182089	20030626
	JP 2005104956	A2	20050421	JP 2003-423516	20031219
PRAI	JP 2002-373531	A	20021225		
	JP 2002-373625	A	20021225		
	JP 2003-182089	A	20030626		
	JP 2003-315010	A	20030908		

OS MARPAT 142:306448
AB An onium salt compound having a cation moiety of formula I (A = I, S; m = 1 or 2; n = 0 or 1; x = 1-10; and Ar1, Ar2 = aromatic hydrocarbon group; and P = -O-SO2R, -O-S(O)R, -SO2R; R = H, (substituted) alkyl group, or a (substituted) alicyclic hydrocarbon group)is disclosed. The onium salt compound is suitable as a photoacid generator for photoresists of a pos.-tone radiation-sensitive resin composition The pos.-tone radiation-sensitive resin composition containing this compound is useful as a chemical-amplified photoresist exhibiting high resolution at high sensitivity, responsive to various radiations, and having outstanding storage stability.
IT **847799-76-2P**
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(preparation of onium salt compound as photoacid generator for radiation-sensitive resin composition)
RN 847799-76-2 CAPLUS
CN Sulfonium, [4-(1,4-dioxaspiro[4.5]dec-7-ylsulfonyl)phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

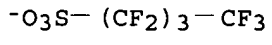
CM 1

CRN 847799-75-1
CMF C26 H27 O4 S2



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S



10/743,809, ~~9/5/05~~ 9/5/05, CA Reg. File struc. search of , RQA

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L3            13 S L2

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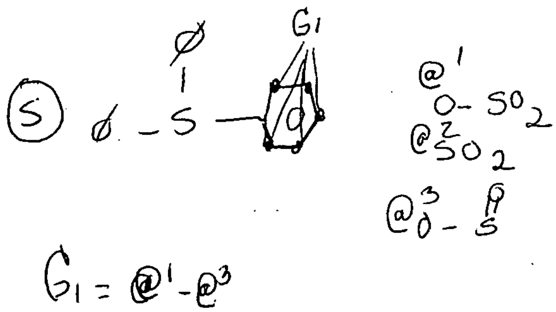


VPA.

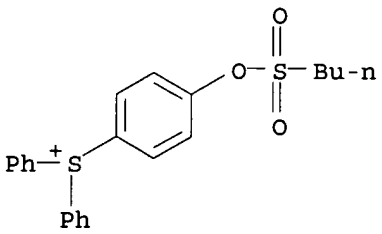
L3 ANSWER 1 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2005:219970 CAPLUS
DN 142:306448
TI Onium salt compound and radiation-sensitive resin composition
IN Yoneda, Eiji; Wang, Yong; Nishimura, Yukio
PA Japan
SO U.S. Pat. Appl. Publ., 85 pp.
CODEN: USXXCO
DT Patent
LA English
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2005053861	A1	20050310	US 2003-743809	20031224
	JP 2004250427	A2	20040909	JP 2003-182089	20030626
	JP 2005104956	A2	20050421	JP 2003-423516	20031219
PRAI	JP 2002-373531	A	20021225		
	JP 2002-373625	A	20021225		
	JP 2003-182089	A	20030626		
	JP 2003-315010	A	20030908		

OS MARPAT 142:306448
AB An onium salt compound having a cation moiety of formula I (A = I, S; m = 1 or 2; n = 0 or 1; x = 1-10; and Ar1, Ar2 = aromatic hydrocarbon group; and P = -O-SO2R, -O-S(O)R, -SO2R; R = H, (substituted) alkyl group, or a (substituted) alicyclic hydrocarbon group)is disclosed. The onium salt compound is suitable as a photoacid generator for photoresists of a pos.-tone radiation-sensitive resin composition The pos.-tone radiation-sensitive resin composition containing this compound is useful as a chemical-amplified photoresist exhibiting high resolution at high sensitivity, responsive to various radiations, and having outstanding storage stability.
IT **753454-43-2P 753454-51-2P 847799-93-3P**
847799-95-5P 847799-97-7P 847799-99-9P
847800-01-5P 847800-03-7P 847800-05-9P
847800-07-1P 847800-09-3P 847800-11-7P
847800-12-8P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(onium salt compound as photoacid generator for radiation-sensitive resin composition)
RN 753454-43-2 CAPLUS
CN Sulfonium, [4-[(butylsulfonyl)oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 753454-42-1
CMF C22 H23 O3 S2



CM 2

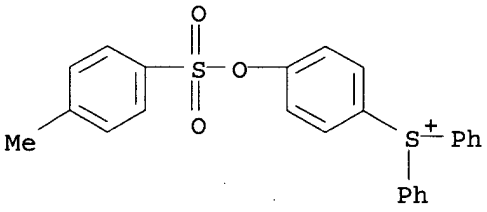
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 753454-51-2 CAPLUS
CN Sulfonium, [4-[[(4-methylphenyl)sulfonyl]oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 753454-50-1
CMF C25 H21 O3 S2



CM 2

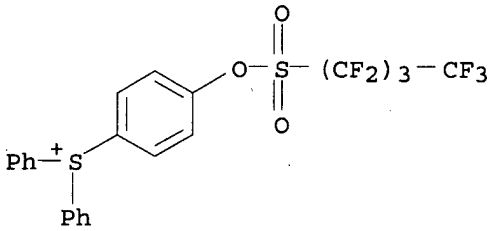
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847799-93-3 CAPLUS
CN Sulfonium, [4-[[(nonafluorobutyl)sulfonyl]oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847799-92-2
CMF C22 H14 F9 O3 S2



CM 2

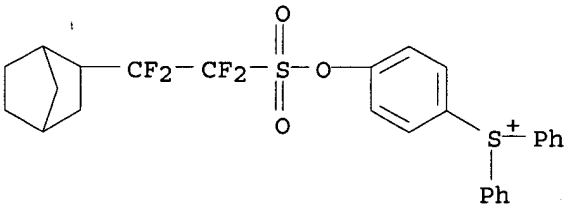
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847799-95-5 CAPLUS
CN Sulfonium, [4-[[(2-bicyclo[2.2.1]hept-2-yl-1,1,2,2-tetrafluoroethyl)sulfonyl]oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847799-94-4
CMF C27 H25 F4 O3 S2



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S

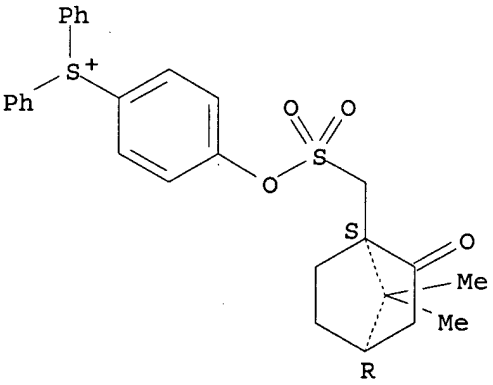
$^{-}O_3S-(CF_2)_3-CF_3$

RN 847799-97-7 CAPLUS
CN Sulfonium, [4-[[[[(1S,4R)-7,7-dimethyl-2-oxobicyclo[2.2.1]hept-1-yl]methyl]sulfonyl]oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847799-96-6
CMF C28 H29 O4 S2

Absolute stereochemistry.



CM 2

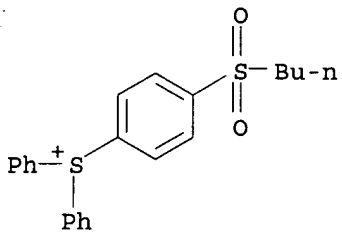
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847799-99-9 CAPLUS
CN Sulfonium, [4-(butylsulfonyl)phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847799-98-8
CMF C22 H23 O2 S2



CM 2

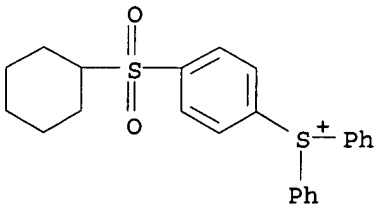
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847800-01-5 CAPLUS
CN Sulfonium, [4-(cyclohexylsulfonyl)phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847800-00-4
CMF C24 H25 O2 S2



CM 2

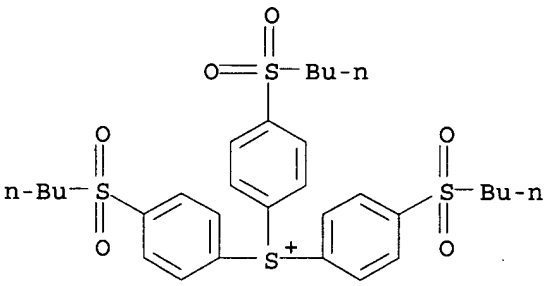
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847800-03-7 CAPLUS
CN Sulfonium, tris[4-(butylsulfonyl)phenyl]-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847800-02-6
CMF C30 H39 O6 S4



CM 2

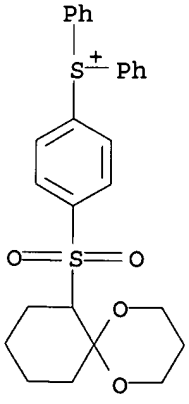
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847800-05-9 CAPLUS
CN Sulfonium, [4-(1,5-dioxaspiro[5.5]undec-7-ylsulfonyl)phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847800-04-8
CMF C27 H29 O4 S2



CM 2

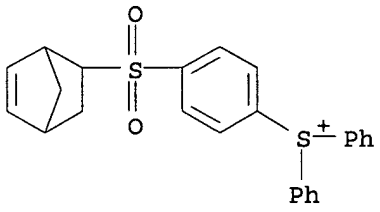
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847800-07-1 CAPLUS
CN Sulfonium, [4-(bicyclo[2.2.1]hept-5-en-2-ylsulfonyl)phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847800-06-0
CMF C25 H23 O2 S2



CM 2

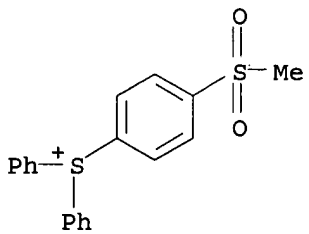
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847800-09-3 CAPLUS
CN Sulfonium, [4-(methylsulfonyl)phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847800-08-2
CMF C19 H17 O2 S2



CM 2

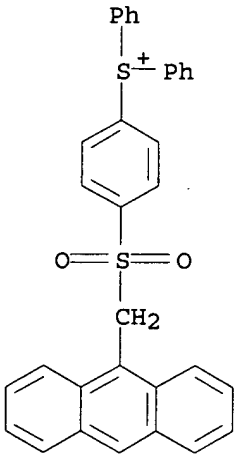
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847800-11-7 CAPLUS
CN Sulfonium, [4-[(9-anthracenylmethyl)sulfonyl]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 847800-10-6
CMF C33 H25 O2 S2



CM 2

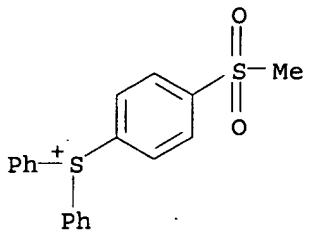
CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

RN 847800-12-8 CAPLUS
CN Sulfonium, [4-(methylsulfonyl)phenyl]diphenyl-, salt with α,α,β,β-tetrafluorobicyclo[2.2.1]heptane-2-ethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

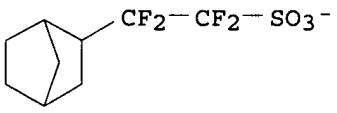
CM 1

CRN 847800-08-2
CMF C19 H17 O2 S2



CM 2

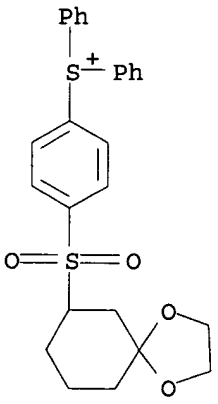
CRN 474516-37-5
CMF C9 H11 F4 O3 S



IT **847799-76-2P**
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(preparation of onium salt compound as photoacid generator for radiation-sensitive resin composition)
RN 847799-76-2 CAPLUS
CN Sulfonium, [4-(1,4-dioxaspiro[4.5]dec-7-ylsulfonyl)phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

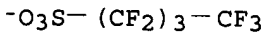
CM 1

CRN 847799-75-1
CMF C26 H27 O4 S2



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S



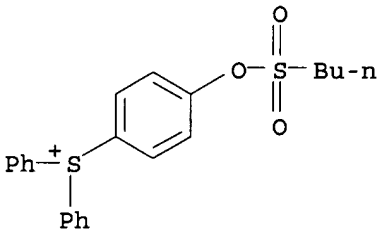
L3 ANSWER 2 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2004:741785 CAPLUS
DN 141:268555
TI Onium salts for radiation-sensitive acid generator for positive photoresist compositions
IN Yoneda, Eiji; Nishimura, Yukio; Wang, Yong
PA JSR Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 48 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004250427	A2	20040909	JP 2003-182089	20030626
	US 2005053861	A1	20050310	US 2003-743809	20031224
PRAI	JP 2002-373625	A	20021225		
	JP 2002-373531	A	20021225		
	JP 2003-182089	A	20030626		
	JP 2003-315010	A	20030908		

OS MARPAT 141:268555
AB The onium salt has cationic portion represented with (Ar2)n-A+-(Ar1)m-(OZ)x (A = I, S; m = 1,2 ; n = 0, 1; (m+n) = 2; x = integer 1-10; Ar1-2 = mono-valent C6-20 aromatic hydrocarbon, mono-valent C3-20 heterocyclic ring, 3-8 membered ring residue with Ar1, Ar2, and A; Z = -SO2R1, -S(O)R2; R1-2 = H, C1-20 alkyl, mono-valent C3-20 alicyclic, etc.). The onium salt provides photoresist composition of high sensitivity and good storageability.
IT **753454-43-2P 753454-45-4P 753454-47-6P**
753454-49-8P 753454-51-2P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(onium salts for radiation-sensitive acid generator for pos. photoresist compns.)
RN 753454-43-2 CAPLUS
CN Sulfonium, [4-[(butylsulfonyl)oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

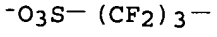
CM 1

CRN 753454-42-1
CMF C22 H23 O3 S2



CM 2

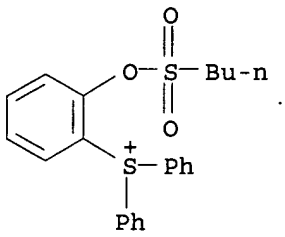
CRN 45187-15-3
CMF C4 F9 O3 S



RN 753454-45-4 CAPLUS
CN Sulfonium, [2-[(butylsulfonyl)oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

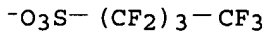
CM 1

CRN 753454-44-3
CMF C22 H23 O3 S2



CM 2

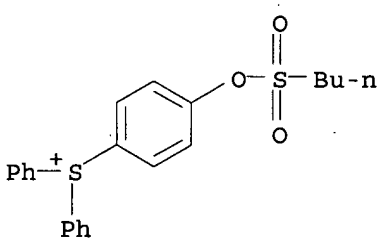
CRN 45187-15-3
CMF C4 F9 O3 S



RN 753454-47-6 CAPLUS
CN Sulfonium, [4-[(butylsulfonyl)oxy]phenyl]diphenyl-, salt with α,α,β,β-tetrafluorobicyclo[2.2.1]heptane-2-ethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

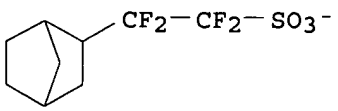
CM 1

CRN 753454-42-1
CMF C22 H23 O3 S2



CM 2

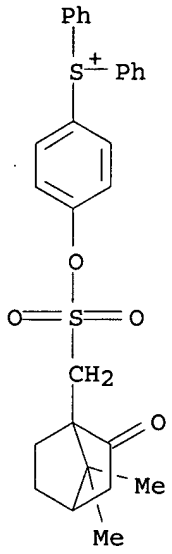
CRN 474516-37-5
CMF C9 H11 F4 O3 S



RN 753454-49-8 CAPLUS
CN Sulfonium, [4-[[[(7,7-dimethyl-2-oxobicyclo[2.2.1]hept-1-yl)methyl]sulfonyl]oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

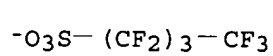
CM 1

CRN 753454-48-7
CMF C28 H29 O4 S2



CM 2

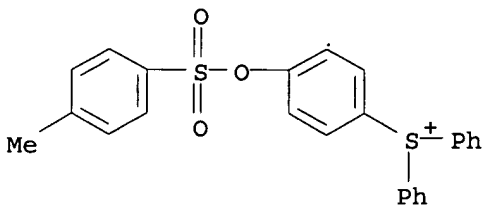
CRN 45187-15-3
CMF C4 F9 O3 S



RN 753454-51-2 CAPLUS
CN Sulfonium, [4-[[(4-methylphenyl)sulfonyl]oxy]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

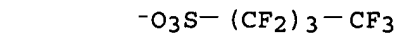
CM 1

CRN 753454-50-1
CMF C25 H21 O3 S2



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S



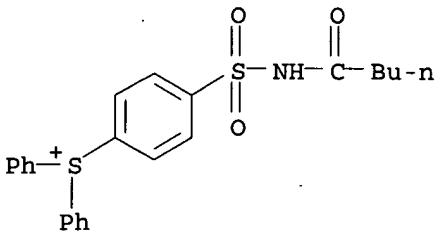
L3 ANSWER 3 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:853314 CAPLUS
DN 139:343479
TI Sulfonium compounds as radiation-sensitive acid generators and resist compositions containing them
IN Kodama, Kunihiko
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 66 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2003307839	A2	20031031	JP 2002-112372	20020415
PRAI JP 2002-112372		20020415		

OS MARPAT 139:343479
AB (Ba)mAaS+Y1Y2 X- (I; Y1, Y2 = alkyl, aryl, aralkyl, heterocyclyl, oxoalkyl, oxoaralkyl; Y1 and Y2 may be bonded together to form a ring; Aa = direct bond, organic group; Ba = group having CONRa or SO2NRa; Ra = H, alkyl; m = 1-3; X- = nonnucleophilic anion), which generate acids upon irradiation with actinic ray or radiation, are claimed. Also claimed are resist compns. containing I, pos.-working resist compns. containing I and resins which are decomposed by acids to show increased solubility to an alkaline developer, neg.-working resist compns. containing I, water-insol. alkali-soluble resins, and crosslinking agents which crosslink to the alkali-soluble resins by acids, etc. The resist compns. containing I show high sensitivity, resolution, and good profile, and are especially suitable for irradiation with far-UV and electron beam.
IT **617692-49-6**
RL: CAT (Catalyst use); USES (Uses)
(preparation of sulfonium compds. having amide or sulfonamide linkage as radiation-sensitive acid generators and resist compns. containing them)
RN 617692-49-6 CAPLUS
CN Sulfonium, [4-[[(1-oxopentyl)amino]sulfonyl]phenyl]diphenyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

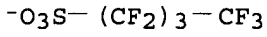
CM 1

CRN 617692-48-5
CMF C23 H24 N O3 S2



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S



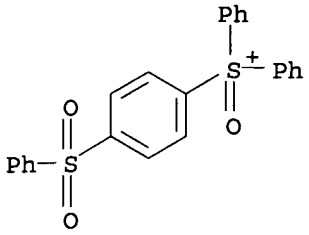
L3 ANSWER 4 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1997:599494 CAPLUS
DN 127:191198
TI Photoinitiators and photoinitiator compositions and photocurable hybrid resin compositions
IN Toba, Yasumasa; Tanaka, Yasuhiro; Yasuike, Madoka
PA Toyo Ink Mfg. Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 31 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 09183961	A2	19970715	JP 1995-342494	19951228
PRAI JP 1995-342494		19951228		

OS MARPAT 127:191198
AB The photoinitiator compns., having a high curing rate, contain sulfoxonium borates R1R2R3S+(O)·(BXmZn)- (R1-R3 = C6-20 aryl which may be substituted by halo, OH, NO2, CN, NH2, alkyl, alkoxy, aralkyloxy, aryl, aryloxy, aralkyl group; X = F, Cl; Z = Ph group substituted by ≥2 F, CN, NO2, CF3; m = 0-3; n = 1-4; m + n = 4). Thus, a composition containing 100 parts an epoxy resin (ERL 4221) and 3 parts triphenylsulfoxonium tetrakis(pentafluorophenyl)borate was irradiated by UV to give a cured film.
IT **194293-67-9 194293-75-9**
RL: CAT (Catalyst use); USES (Uses)
(sulfoxonium borate photoinitiators and photocurable hybrid resin compns.)
RN 194293-67-9 CAPLUS
CN Sulfoxonium, diphenyl[4-(phenylsulfonyl)phenyl]-, tetrakis(pentafluorophenyl)borate(1-) (9CI) (CA INDEX NAME)

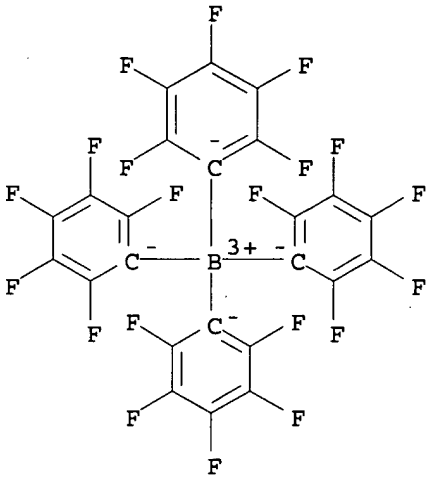
CM 1

CRN 139572-76-2
CMF C24 H19 O3 S2



CM 2

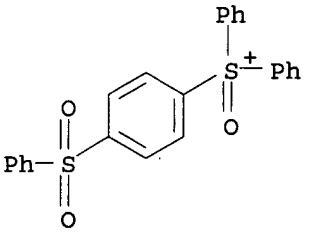
CRN 47855-94-7
CMF C24 B F20
CCI CCS



RN 194293-75-9 CAPLUS
CN Sulfoxonium, diphenyl[4-(phenylsulfonyl)phenyl]-, tetrakis[4-(trifluoromethyl)phenyl]borate(1-) (9CI) (CA INDEX NAME)

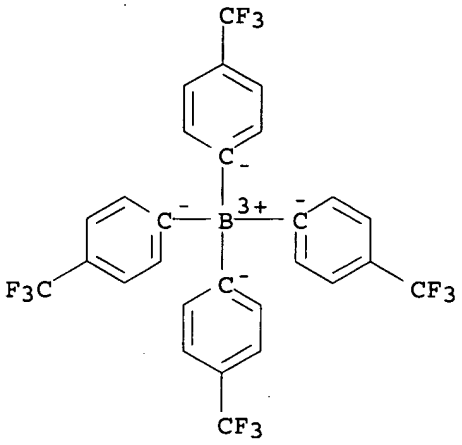
CM 1

CRN 139572-76-2
CMF C24 H19 O3 S2



CM 2

CRN 47823-82-5
CMF C28 H16 B F12
CCI CCS



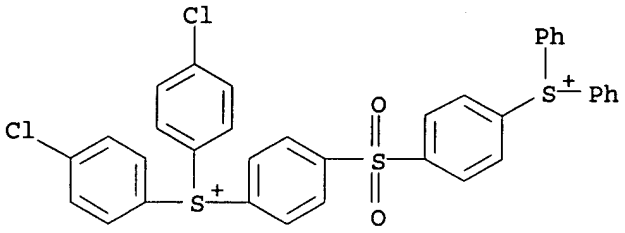
L3 ANSWER 5 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1996:256323 CAPLUS
DN 124:318806
TI Photopolymerization initiators, radiation-curable compositions, and their cured products
IN Abe, Tetsuya; Yokoshima, Minoru
PA Nippon Kayaku Kk, Japan
SO Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08041116	A2	19960213	JP 1994-193778	19940727
	JP 3424772	B2	20030707		
PRAI	JP 1994-193778		19940727		

OS MARPAT 124:318806
AB Sulfonium- and sulfoxonium-type photopolymn. initiators are synthesized and are used in radiation curable epoxy resins. Thus, compound I was oxidized with hydrogen peroxide to give compound II; II 1.5, Celloxide 2021 80, and EHPE 3150 20 parts were mixed and cured by UV to show transparency, storage stability, gloss, no odor, and tack free 23 mJ/cm2.
IT **176310-56-8P 176310-58-0P 176310-62-6P**
176310-64-8P 176310-66-0P
RL: CAT (Catalyst use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(preparation of photopolymn. initiators and radiation-curable compns.)
RN 176310-56-8 CAPLUS
CN Sulfonium, bis(4-chlorophenyl)[4-[[4-(diphenylsulfonio)phenyl]sulfonyl]phenyl]-, bis[hexafluorophosphate(1-)] (9CI) (CA INDEX NAME)

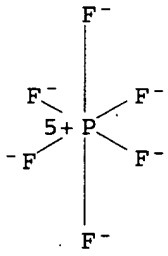
CM 1

CRN 176310-55-7
CMF C36 H26 Cl2 O2 S3



CM 2

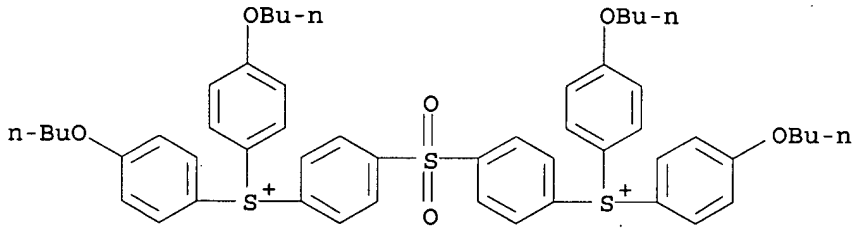
CRN 16919-18-9
CMF F6 P
CCI CCS



RN 176310-58-0 CAPLUS
CN Sulfonium, (sulfonyldi-4,1-phenylene)bis[bis(4-butoxyphenyl)-, bis[(OC-6-11)-hexafluoroantimonate(1-)] (9CI) (CA INDEX NAME)

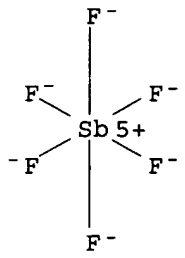
CM 1

CRN 176310-57-9
CMF C52 H60 O6 S3



CM 2

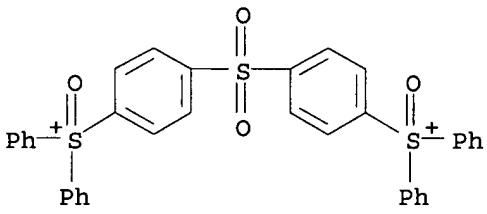
CRN 17111-95-4
CMF F6 Sb
CCI CCS



RN 176310-62-6 CAPLUS
CN Sulfoxonium, (sulfonyldi-4,1-phenylene)bis[diphenyl-, bis[hexafluorophosphate(1-)] (9CI) (CA INDEX NAME)

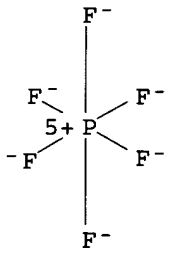
CM 1

CRN 176310-61-5
CMF C36 H28 O4 S3



CM 2

CRN 16919-18-9
CMF F6 P
CCI CCS

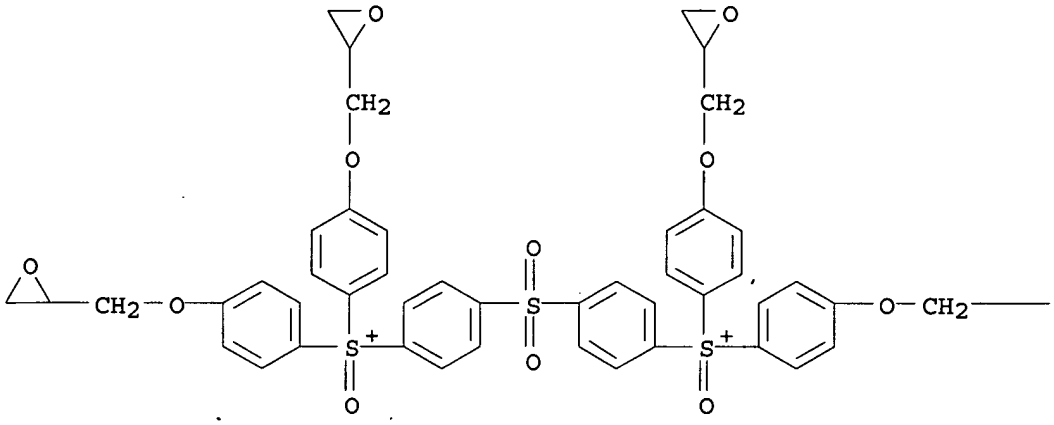


RN 176310-64-8 CAPLUS
CN Sulfoxonium, (sulfonyldi-4,1-phenylene)bis[bis[4-(oxiranylmethoxy)phenyl]-, bis[(OC-6-11)-hexafluoroantimonate(1-)] (9CI) (CA INDEX NAME)

CM 1

CRN 176310-63-7
CMF C48 H44 O12 S3

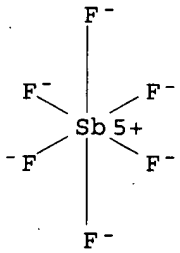
PAGE 1-A



PAGE 1-B

CM 2

CRN 17111-95-4
CMF F6 Sb
CCI CCS

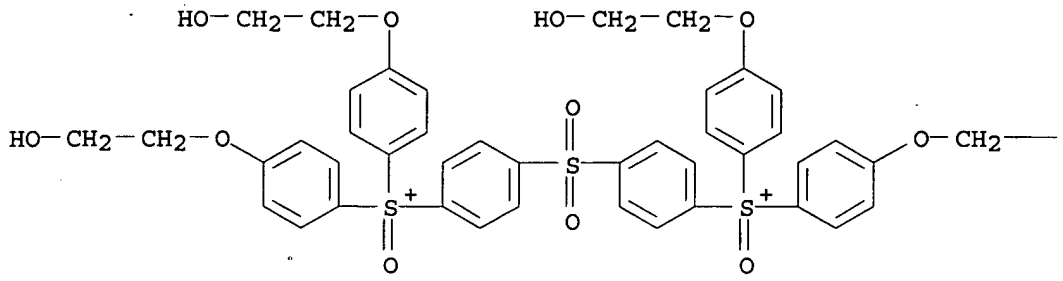


RN 176310-66-0 CAPLUS
CN Sulfoxonium, (sulfonyldi-4,1-phenylene)bis[bis[4-(2-hydroxyethoxy)phenyl]-, bis[(OC-6-11)-hexafluoroantimonate(1-)] (9CI) (CA INDEX NAME)

CM 1

CRN 176310-65-9
CMF C44 H44 O12 S3

PAGE 1-A

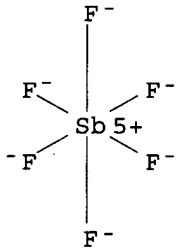


PAGE 1-B

— CH_2 — OH

CM 2

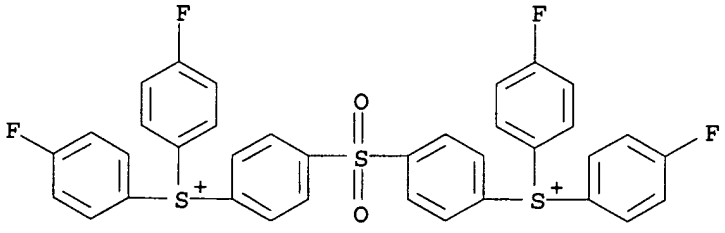
CRN 17111-95-4
CMF F6 Sb
CCI CCS



IT **176310-52-4P 176310-60-4P**
RL: CAT (Catalyst use); IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent); USES (Uses)
(preparation of photopolymn. initiators and radiation-curable compns.)
RN 176310-52-4 CAPLUS
CN Sulfonium, (sulfonyldi-4,1-phenylene)bis[bis(4-fluorophenyl)-, bis[(OC-6-11)-hexafluoroantimonate(1-)] (9CI) (CA INDEX NAME)

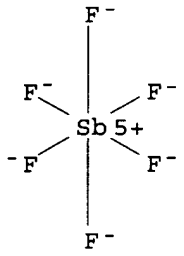
CM 1

CRN 176310-51-3
CMF C36 H24 F4 O2 S3



CM 2

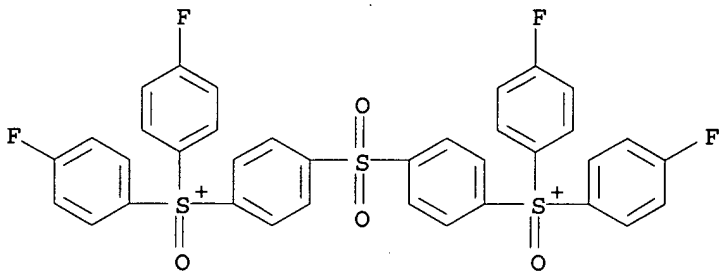
CRN 17111-95-4
CMF F6 Sb
CCI CCS



RN 176310-60-4 CAPLUS
CN Sulfoxonium, (sulfonyldi-4,1-phenylene)bis[bis(4-fluorophenyl)-, bis[(OC-6-11)-hexafluoroantimonate(1-)] (9CI) (CA INDEX NAME)

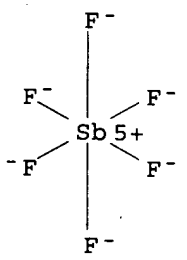
CM 1

CRN 176310-59-1
CMF C36 H24 F4 O4 S3



CM 2

CRN 17111-95-4
CMF F6 Sb
CCI CCS



L3 ANSWER 6 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1996:256143 CAPLUS
DN 124:292462

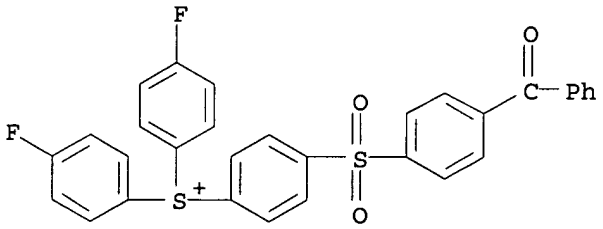
TI Cationic photoinitiators and photocurable compositions and cured products
IN Abe, Tetsuya; Yokoshima, Minoru
PA Nippon Kayaku Kk, Japan
SO Jpn. Kokai Tokkyo Koho, 14 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08027209	A2	19960130	JP 1994-189079	19940720
	JP 3424771	B2	20030707		
PRAI	JP 1994-189079		19940720		

OS MARPAT 124:292462
AB The compns. useful for ink and coating applications, and giving odorless cured products with good gloss, comprise cationically polymerizable compds., and specific sulfonium compds. or sulfoxonium compds. as photoinitiators. Thus, a composition containing PhCO-p-C6H4SO2-p-C6H4S+(C6H4-p-F)2·PF6- 1.5, Celloxide 2021 (alicyclic epoxy resin) 2021 80, and EHPE 3150 (alicyclic epoxy resin) 20 parts was applied on an Al test panel, and irradiated by UV to give coatings with good gloss.
IT **175840-84-3P 175840-92-3P 175840-94-5P**
RL: CAT (Catalyst use); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
(sulfonium and sulfoxonium compds. as cationic photoinitiators and photocurable compns. and cured products)
RN 175840-84-3 CAPLUS
CN Sulfonium, [4-[(4-benzoylphenyl)sulfonyl]phenyl]bis(4-fluorophenyl)-, hexafluorophosphate(1-) (9CI) (CA INDEX NAME)

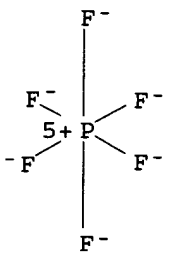
CM 1

CRN 175840-83-2
CMF C31 H21 F2 O3 S2



CM 2

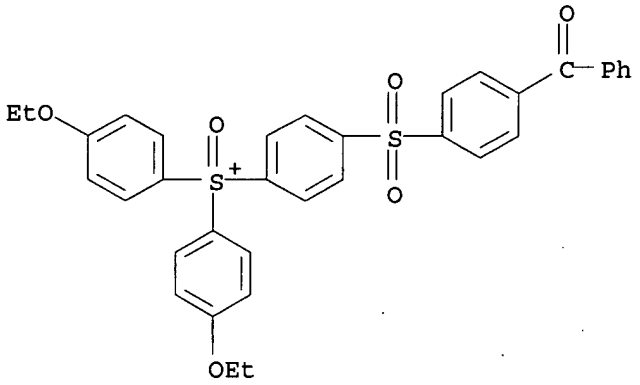
CRN 16919-18-9
CMF F6 P
CCI CCS



RN 175840-92-3 CAPLUS
CN Sulfoxonium, [4-[(4-benzoylphenyl)sulfonyl]phenyl]bis(4-ethoxyphenyl)-, hexafluorophosphate(1-) (9CI) (CA INDEX NAME)

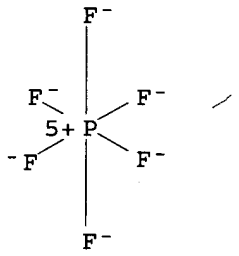
CM 1

CRN 175840-91-2
CMF C35 H31 O6 S2



CM 2

CRN 16919-18-9
CMF F6 P
CCI CCS

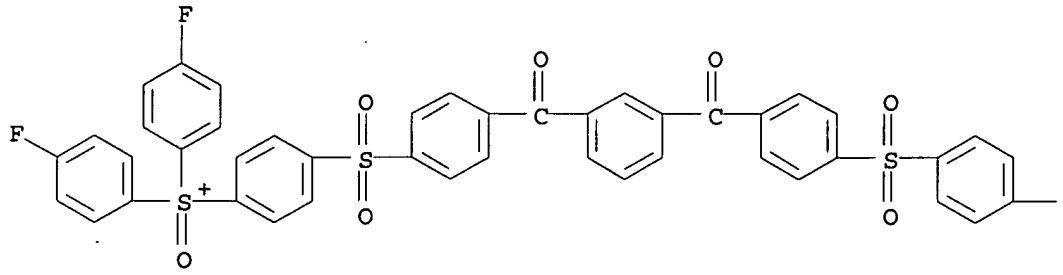


RN 175840-94-5 CAPLUS
CN Sulfoxonium, [1,3-phenylenebis(carbonyl-4,1-phenylenesulfonyl-4,1-phenylene)]bis[bis(4-fluorophenyl)-, bis[(OC-6-11)-hexafluoroantimonate(1-)] (9CI) (CA INDEX NAME)

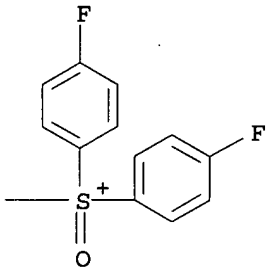
CM 1

CRN 175840-93-4
CMF C56 H36 F4 O8 S4

PAGE 1-A

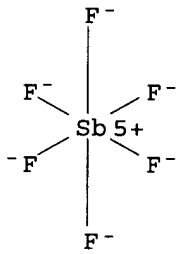


PAGE 1-B



CM 2

CRN 17111-95-4
CMF F6 Sb
CCI CCS



L3 ANSWER 7 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1992:131247 CAPLUS
DN 116:131247
TI Preparation of triarylsulfoxonium salts and their use as initators for cationic photopolymerization
IN Irving, Edward; Taylor, David Alan; Lunn, Robert James; Innocenzi, John Paul; Haines, Alan Hugh
PA CIBA Ltd., Switz.
SO Brit. UK Pat. Appl., 24 pp.
CODEN: BAXXDU
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	GB 2238787	A1	19910612	GB 1989-27530	19891206
	GB 2238787	B2	19930303		

	JP 03271270	A2	19911203	JP 1990-333442	19901129
	DE 4038536	A1	19910613	DE 1990-4038536	19901203
	CA 2031428	AA	19910607	CA 1990-2031428	19901204
	FR 2655338	A1	19910607	FR 1990-15147	19901204
	FR 2655338	B1	19921002		
	US 5576461	A	19961119	US 1990-622905	19901206

PRAI GB 1989-27530 A 19891206

OS MARPAT 116:131247

AB R1R2R3S+O X- [I; R1, R2, R3 = (substituted) C6-10 aryl, X = anion], useful as initiators for cationic polymerization of compds. such as diepoxides in the manufacture of coatings, are prepared by oxidation of the corresponding sulfonium salts using a peracid under basic conditions in a nonketone solvent. Use of the basic conditions and nonketone solvent improves the yield and eliminates contamination of the product with the starting material. Thus, a solution of 5.1 g NaOH and 6.7 g 30% aqueous H2O2 solution in 50 mL water was added dropwise to 300 mL MeOH containing 5.6 g (4-MeOC6H4)Ph2SPF6 and 6.1 g p-toluenesulfonyl chloride at 15° with stirring, and the mixture was allowed to warm to room temperature overnight to give 84% yield I (R1 = 4-MeOC6H4, R2 = R3 = Ph, X = PF6) (II). Irradiation of a mixture containing 100 parts bisphenol A diglycidyl ether and 3 parts II on tin plate with a 5000-W metal halide lamp 75 cm from the plate provided a tack-free coating in 2 mins.

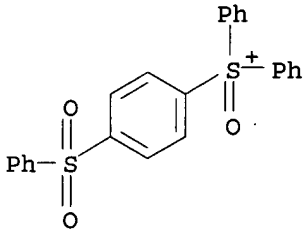
IT **139572-77-3P 139572-79-5P**
RL: PREP (Preparation)
(manufacture of, for cationic photopolymn. catalysts)

RN 139572-77-3 CAPLUS

CN Sulfoxonium, diphenyl[4-(phenylsulfonyl)phenyl]-, hexafluorophosphate(1-) (9CI) (CA INDEX NAME)

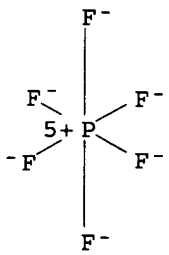
CM 1

CRN 139572-76-2
CMF C24 H19 O3 S2



CM 2

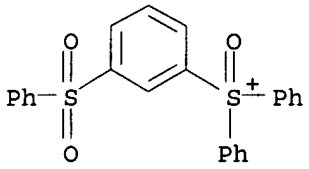
CRN 16919-18-9
CMF F6 P
CCI CCS



RN 139572-79-5 CAPLUS
CN Sulfoxonium, diphenyl[3-(phenylsulfonyl)phenyl]-, hexafluorophosphate(1-) (9CI) (CA INDEX NAME)

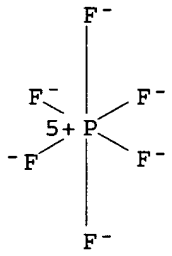
CM 1

CRN 139572-78-4
CMF C24 H19 O3 S2



CM 2

CRN 16919-18-9
CMF F6 P
CCI CCS

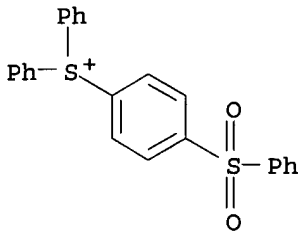


L3 ANSWER 8 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1985:167245 CAPLUS
DN 102:167245
TI Recent advances in thermally and photochemically initiated cationic polymerization
AU Crivello, James V.; Lee, J. L.
CS Gen. Electr. Corp. Res. and Dev., Schenectady, NY, 12301, USA
SO Polymer Journal (Tokyo, Japan) (1985), 17(1), 73-83
CODEN: POLJB8; ISSN: 0032-3896
DT Journal
LA English
AB Classes of arylsulfonium salts are discussed which have enhanced efficiency as photoinitiators or thermal initiators of cationic polymerization One of these compds., p-PhSC6H4SPh2+AsF6- [75482-17-6], was identified as a component of the Friedel-Crafts reaction of C6H6 with S2Cl2. Similar compds., of formula ArSPh2+AsF6- (e.g., Ar = p-PhOC6H4, m-PhSC6H4, and p-PhSO2C6H4) and cyclic analogs (e.g., S-phenyldibenzothiophenium hexafluoroarsenate [82617-08-1]), were also prepared and characterized. Other classes (e.g., dialkylphenacylsulfonium salts, ArCOCH2SR2+X-) are also described; one class, characterized by 4-hydroxy-3,5-dimethoxyphenyldimethylsulfonium hexafluorophosphate [95896-72-3], is especially suited as thermal initiators. The activities of the initiators were tested in the cationic polymns. of limonene dioxide, cyclohexene oxide, and styrene oxide.
IT **75482-29-0**
RL: USES (Uses)

(photoinitiators, for cationic polymerization of epoxides)
RN 75482-29-0 CAPLUS
CN Sulfonium, diphenyl[4-(phenylsulfonyl)phenyl]-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

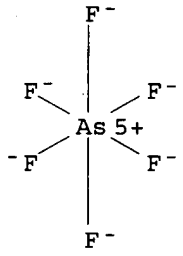
CM 1

CRN 47572-95-2
CMF C24 H19 O2 S2



CM 2

CRN 16973-45-8
CMF As F6
CCI CCS



L3 ANSWER 9 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1983:180499 CAPLUS
DN 98:180499
TI Triarylsulfonium salts
IN Crivello, James V.; Lee, Julia L.
PA General Electric Co., USA
SO U.S., 8 pp. Cont.-in-part of U.S. Ser. No. 79,692, abandoned.
CODEN: USXXAM
DT Patent
LA English
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 4374066	A	19830215	US 1980-200769	19801027
	ZA 8005273	A	19811125	ZA 1980-5273	19800826
	GB 2061280	A	19810513	GB 1980-29024	19800909
	GB 2061280	B2	19840516		
	CA 1120181	A1	19820316	CA 1980-361443	19800925
	FR 2466457	A1	19810410	FR 1980-20689	19800926
	FR 2466457	B1	19850308		
	JP 56055420	A2	19810516	JP 1980-133103	19800926
	JP 63036332	B4	19880720		
	ES 495420	A1	19811016	ES 1980-495420	19800926

	AU 8062780	A1	19810409	AU 1980-62780	19800929
	AU 539699	B2	19841011		
	BR 8006335	A	19810414	BR 1980-6335	19800929
PRAI	US 1979-79692	A2	19790928		

AB Triarylsulfonium salts such as I [75482-17-6] are prepared by a method based on the reaction of an aromatic hydrocarbon S2Cl2, and Cl in the presence of a Friedel-Crafts catalyst. The triarylsulfonium salts are used as cationic photoinitiaters to effect the deep-section cure of organic resin compns. Thus, a mixture of Ph2S [139-66-2] 37.2, AlCl3 13.34, and Cl 9.5 parts was stirred and poured onto 500 parts ice. The semisolid was washed with H2O. Then 27.8 parts AsF6- K+ and 500 parts H2O were added to the residue and the mixture stirred at 30° for 1 h. The product was washed with H2O then with anhydrous Et2O and dried at 60° for 16 h. The product was then recrystd. from 95% EtOH to give 31% yield of I having m.p. 77-87°. Films from a 3% solution of I in 3,4-epoxycyclohexylmethyl 3',4'-epoxycyclohexane carboxylate [2386-87-0] were radiation-cured in 1 min to a maximum thickness of 50 mils, compared with 15 mils for a similar film containing Ph3S+ AsF6-.

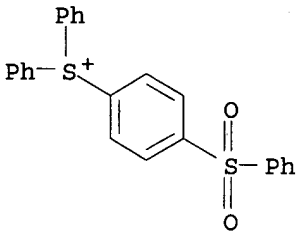
IT **75482-29-0P**
RL: PREP (Preparation)
(preparation of, as photoinitiators for deep cure of polymers)

RN 75482-29-0 CAPLUS

CN Sulfonium, diphenyl[4-(phenylsulfonyl)phenyl]-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

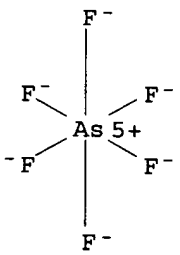
CM 1

CRN 47572-95-2
CMF C24 H19 O2 S2



CM 2

CRN 16973-45-8
CMF As F6
CCI CCS



L3 ANSWER 10 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1981:516453 CAPLUS
DN 95:116453

TI Deep-setting photohardenable compositions
IN Crivello, James Vincent; Lam, Julia Hingwai
PA General Electric Co., USA
SO Ger. Offen., 23 pp.
CODEN: GWXXBX
DT Patent
LA German
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3035807	A1	19810409	DE 1980-3035807	19800923
	DE 3035807	C2	19930401		
	ZA 8005273	A	19811125	ZA 1980-5273	19800826
	GB 2061280	A	19810513	GB 1980-29024	19800909
	GB 2061280	B2	19840516		
	CA 1120181	A1	19820316	CA 1980-361443	19800925
	FR 2466457	A1	19810410	FR 1980-20689	19800926
	FR 2466457	B1	19850308		
	JP 56055420	A2	19810516	JP 1980-133103	19800926
	JP 63036332	B4	19880720		
	ES 495420	A1	19811016	ES 1980-495420	19800926
	AU 8062780	A1	19810409	AU 1980-62780	19800929
	AU 539699	B2	19841011		
	BR 8006335	A	19810414	BR 1980-6335	19800929
PRAI	US 1979-79692	A	19790928		

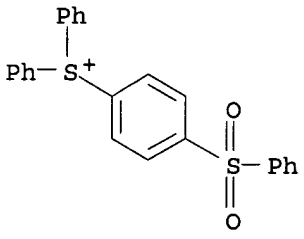
AB The sulfonium compds. 4-RC6H4S+Ph2 AsF6- (R = PhS, PhSO, or PhSO2) and 4-(PhS)C6H4S+Ph2 PF6- [75482-18-7] are useful as initiators for the polymerization of photohardenable epoxy, phenolic, vinyl, and other compds. Thus, Ph2S [139-66-2] was treated with Cl in the presence of AlCl3, and the reaction product was treated with KAsF6 [17029-22-0] to prepare 4-(PhS)C6H4S+Ph2 AsF6- (I) [75482-17-6]. A 3% solution containing 3,4-epoxycyclohexylmethyl 3,4-epoxycyclohexanecarboxylate (II) and I was hardened by UV light as a 1270-μ layer. With Ph3S+ AsF6- as the initiator instead of I, the maximum thickness of II for satisfactory hardening was 254-381 μ.

IT **75482-29-0**
RL: CAT (Catalyst use); USES (Uses)
(catalysts, for photopolymn. and photocrosslinking)

RN 75482-29-0 CAPLUS
CN Sulfonium, diphenyl[4-(phenylsulfonyl)phenyl]-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

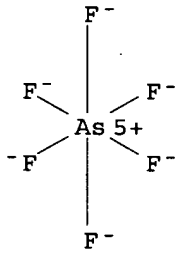
CM 1

CRN 47572-95-2
CMF C24 H19 O2 S2



CM 2

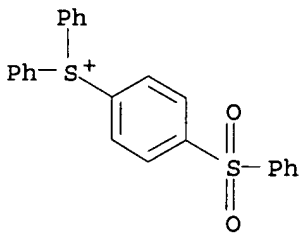
CRN 16973-45-8
CMF As F6
CCI CCS



L3 ANSWER 11 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1980:605102 CAPLUS
DN 93:205102
TI Complex triarylsulfonium salt photoinitiators. II. The preparation of several new complex triarylsulfonium salts and the influence of their structure in photoinitiated cationic polymerization
AU Crivello, J. V.; Lam, J. H. W.
CS Gen. Electr. Corp. Res. Dev. Cent., Schenectady, NY, 12301, USA
SO Journal of Polymer Science, Polymer Chemistry Edition (1980), 18(8), 2697-714
CODEN: JPLCAT; ISSN: 0449-296X
DT Journal
LA English
AB Complex triarylsulfonium salts containing thiophenoxy chromophores were prepared
The effects of the position of the thiophenoxy group on the rate of photolysis and on the photoinitiated cationic polymerization of various monomers were investigated. Salts in which the thiophenoxy group was oxidized to the sulfoxide and the sulfone also were prepared to examine the effects of the oxidation state of the S-bearing chromophore on the efficiencies in photoinitiated cationic polymerization All complex salts having extended conjugation not impeded by positional isomerization or blocked by oxidation of the thiophenoxy group are more reactive than the corresponding triphenylsulfonium salts in cationic polymerization
IT **75482-29-0**
RL: CAT (Catalyst use); USES (Uses)
(catalysts, for cationic photochem. polymerization)
RN 75482-29-0 CAPLUS
CN Sulfonium, diphenyl[4-(phenylsulfonyl)phenyl]-, hexafluoroarsenate(1-) (9CI) (CA INDEX NAME)

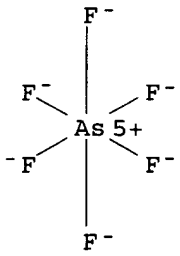
CM 1

CRN 47572-95-2
CMF C24 H19 O2 S2

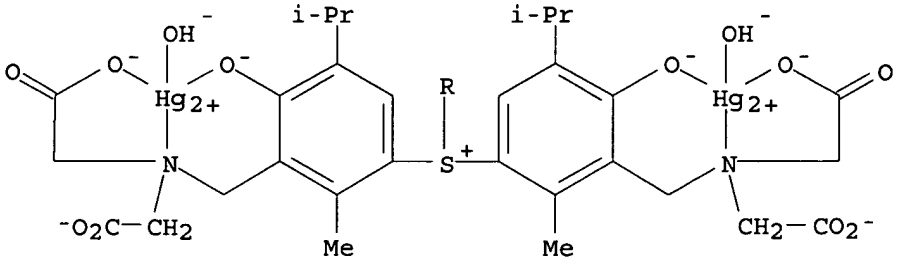


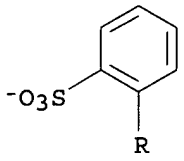
CM 2

CRN 16973-45-8
CMF As F6
CCI CCS



L3 ANSWER 12 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1972:145595 CAPLUS
DN 76:145595
TI Spectrophotometric study of the complexing of mercury(II) with some phthalexons. 2. Complexing of mercury(II) with thymolphthalexons-S
AU Cherkesov, A. I.; Tonkoshkurov, V. S.; Postoronko, A. I.
CS USSR
SO Ftaleksony (1970) 143-50
From: Ref. Zh., Khim. 1971, Abstr. No. 6G11
DT Journal
LA Russian
AB Complexing of Hg2+ with Thymolphthalexon S [disodium salt of 3,3'-bis-[di-(carboxymethyl)]aminomethylthymol-sulfophthalein] (I) (a component of Methylthymol Blue) was studied. The color reaction of Hg2+ with I occurred at pH 3.7-6.5 (optimally at pH 6.0-6.5). The absorption maximum of the complex was at 610 nm (the molar absorptivity was 2.7 + 104). The complex had a 2:1 Hg-I ratio, and the formation constant was 2.54 + 1010.
IT **36490-83-2**
RL: PRP (Properties); FORM (Formation, nonpreparative)
(formation consts. of)
RN 36490-83-2 CAPLUS
CN Mercurate(4-), [μ-[bis[3-[[bis(carboxymethyl)amino]methyl]-4-hydroxy-2-methyl-5-(1-methylethyl)phenyl](2-sulfophenyl)sulfoniumato(9-)]]dihydroxydi-, tetrahydrogen (9CI) (CA INDEX NAME)



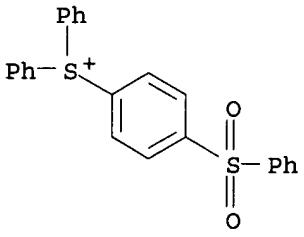


● 4 H^+

L3 ANSWER 13 OF 13 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1972:85504 CAPLUS
DN 76:85504
TI Electrochemistry of organic sulfur compounds. III. Novel anodic synthesis of a sulfonium salt from diphenyl sulfide
AU Uneyama, Kenji; Torii, Sigeru
CS Sch. Eng., Okayama Univ., Okayama, Japan
SO Journal of Organic Chemistry (1972), 37(3), 367-9
CODEN: JOCEAH; ISSN: 0022-3263
DT Journal
LA English
AB Ph2S, dissolved in MeCN containing LiClO4, was electrolyzed at 30° to give diphenyl [p-(phenylthio)phenyl] sulfonium (I), Ph2SO, and 1,4-bis(phenylthio)benzene. Sulfonium salt I predominated in the absence of water, while Ph2SO increased as the concentration of H2O was raised.
IT **32958-91-1P**
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation of)
RN 32958-91-1 CAPLUS
CN Sulfonium, diphenyl[4-(phenylsulfonyl)phenyl]-, perchlorate (9CI) (CA INDEX NAME)

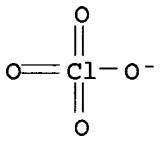
CM 1

CRN 47572-95-2
CMF C24 H19 O2 S2



CM 2

CRN 14797-73-0
CMF Cl O4



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